

PTO-1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. 22 2004 283.003-US	SERIAL NUMBER 10/677,563
	APPLICANT(S) Ye et al.	
	FILING DATE October 2, 2003	GROUP ART UNIT

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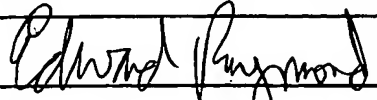
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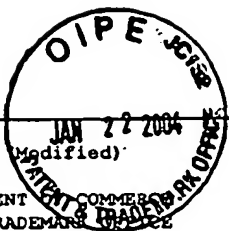
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CP	WO 00/59206	10/2000	PCT			
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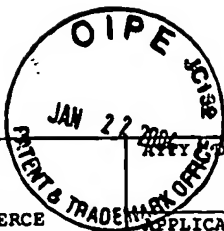
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EXAMINER <i>Edward Rymond</i>	DATE CONSIDERED <i>4/8/04</i>
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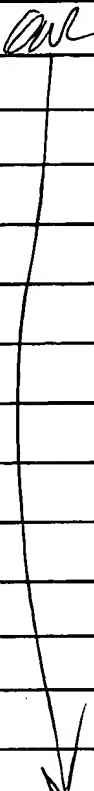
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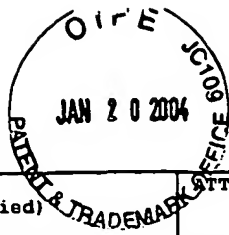
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